

Serial No.

RD-25,993-7

The Examiner is invited to telephone the Applicants' counsel at the number provided below in order to resolve any outstanding issues concerning the present application.

Respectfully submitted,



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ATTACHMENT A

Marked-up versions of amended Claims 4-7 and 57 are provided below.

Marked-up version of Claim 4:

4. (Amended) A method of depositing a plurality of layers on an article, the method comprising steps of:

flowing a plasma gas in a plasma generation chamber in communication with a deposition chamber, the deposition chamber having a lower pressure than the plasma generation chamber, the article being disposed in the deposition chamber;

generating an arc in the plasma generation chamber to create a plasma, which flows into the deposition chamber;

injecting a first material comprising an organometallic material and a first oxidant into the plasma and reacting the first material to form an interlayer on the article, the interlayer comprising a polymerized organosilicon material; and

injecting a second material comprising an organosilicon material and a second oxidant into the plasma and reacting the second material to form a second layer comprising an inorganic ultraviolet absorbing material on the interlayer, the second material comprising a gaseous reagent, wherein the interlayer has a coefficient of thermal expansion that is between that of the substrate and the second layer [The method of claim 1, wherein the first material comprises an organometallic material, the second material comprises an organosilicon material, and the method further comprises the steps of:

injecting an oxidant with the first material; and

injecting an oxidant with the second material].

Marked-up version of Claim 5:

5. (Amended) The method of claim [1]4, wherein the first material or the second material comprises an evaporated elemental metal.

Marked-up version of Claim 6:

6. (Amended) The method of claim [1]4, further comprising the step of injecting a third material into the plasma to form a third layer and reacting the third material to form a third layer comprising an abrasion resistant material on the second layer.

Marked-up version of Claim 7:

7. (Amended) The method of claim 6, wherein the first material comprises [an] a first organosilicon material, the second material comprises an evaporated elemental metal, and the third material comprises [an] a third organosilicon material, and the method further comprises the [steps] step of

[injecting an oxidant with the second material; and]

injecting [an] a third oxidant with the third material.

Marked-up version of Claim 57:

57. (Amended) The method of claim [1]4, wherein the substrate comprises glass.